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PATENT APPLICATION
10/044,076



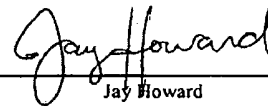
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: H. Ufuk Alpay et al.
Serial No.: 10/044,076
Date Filed: January 11, 2002
Group Art Unit: 1756
Examiner: Mohamedulla, Saleha R.
Title: **DAMAGE RESISTANT PHOTOMASK
CONSTRUCTION**

MAIL STOP - AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

I hereby certify that this correspondence is being deposited with the United States Postal Service as Express Mail No. EV351292059US addressed to: Mail Stop - AF, Commissioner of Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on July 2, 2004.


Jay Howard

Dear Sir:

RESPONSE TO FINAL OFFICE ACTION

In response to the Final Office Action mailed May 5, 2004, Applicants respectfully submit the following amendments set forth below and request favorable action thereon.

Amendments to Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.

DO NOT ENTER
-SKM
8/2/04